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PATENT & TRADEMARK

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PATENT
Att[illegible] No.: AMAT/3417/ETCH/SILICON/JB1

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:
Xu, et al.

Serial No.: 09/352,008

Confirmation No.: 1579

Filed: July 12, 1999

For: NEW METHODOLOGIES TO REDUCE ETCH PROCESS SENSITIVITY TO THE CHAMBER CONDITION OF PLASMA REACTOR

§ Group Art Unit: 1763

§ Examiner: G. A. Goudreau

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TC 1700

Assistant Commissioner for Patents
Washington, D.C. 20231

CERTIFICATE OF MAILING
37 CFR 1.8
I hereby certify that this correspondence is being deposited on 7/26, 2002, with the United States Postal Service as First Class Mail in an envelope addressed to: Assistant Commissioner for Patents, Washington, D.C. 20231.

7/26/02 — Date
[signature] — Signature

Dear Sir:

RESPONSE TO RESTRICTION REQUIREMENT DATED JULY 2, 2002

In response to the Restriction Requirement dated July 2, 2002, having a shortened statutory period for response set to expire on August 1, 2002, Applicants elect claims 6-13 with traverse, and request reconsideration of the restriction requirement for the reasons discussed below. Although Applicant believes that no fee is due in conjunction with this response, the Commissioner is hereby authorized to charge counsel's Deposit Account No. 20-0782/AMAT/3417/BTP, for any fees, including extension of time fees or excess claim fees, required to make this response timely and acceptable to the Office.

REMARKS

This is intended as a full and complete response to the Restriction Requirement dated July 2, 2002.

COPY OF PAPERS ORIGINALLY FILED